

# Saclay workshop R&D for new Bulk structure

- Saclay MPGD workshop
- BULK R&D
  - Double sided bulk
  - Segmented mesh
  - Thin and thick mesh
  - Thick photoresist gap for multimesh bulk
  - Pillar R&D

# Saclay MPGD workshop

The photoresist film (Pyrалux PC) are laminated on the PCB. The maximum width is 600 mm. Two thickness can be used, 50 and 64  $\mu\text{m}$ , with several layer to obtain the amplification gap (typically 128  $\mu\text{m}$ ). The mesh stretched on a frame is laminated with (under) the last layer. The 128  $\mu\text{m}$  amplification gap is theoretical : depending of the pressure of lamination this gap varies between 110 and 120  $\mu\text{m}$ .

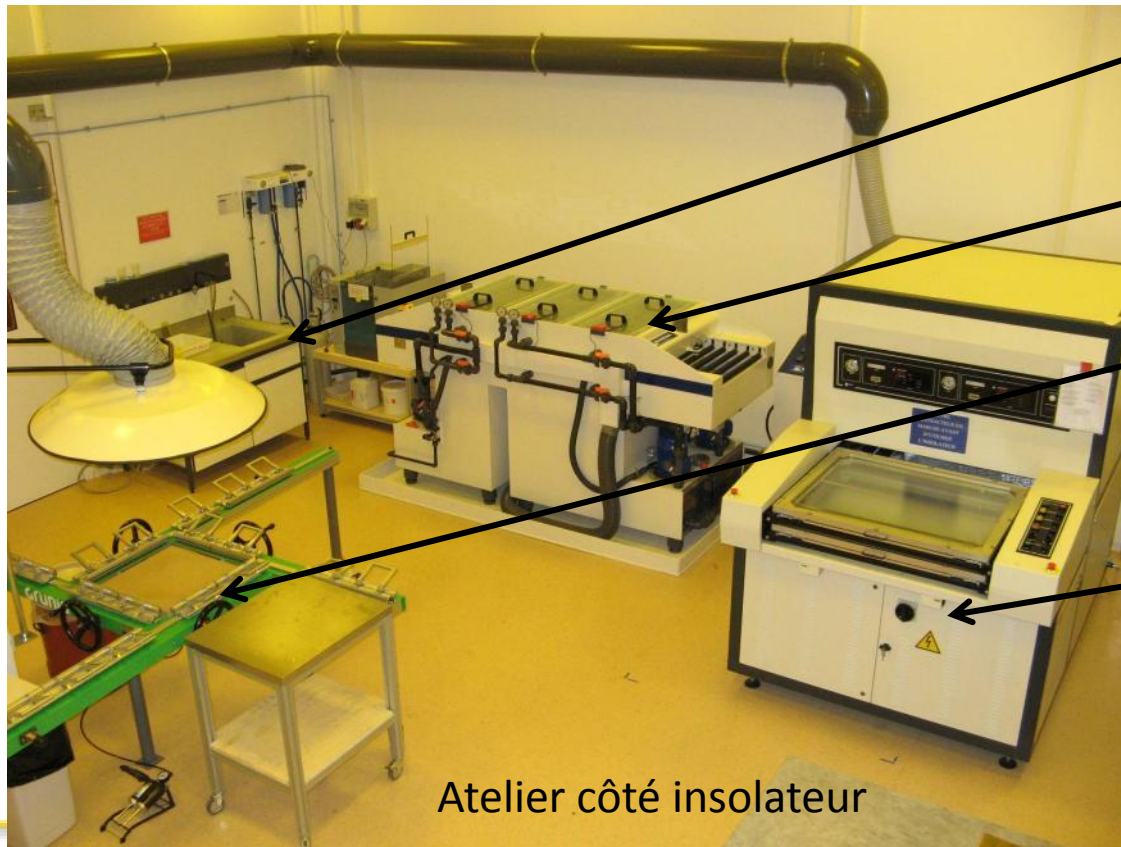
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Oven  
lamineur



# Saclay MPGD workshop

- The goal of the laminator is to polymerize the layers of photoresist that encapsulate the mesh.
- A insulating mask allows to polymerize pillars ,on the active area and , borders and zone for HV contact. The important parameter is the insulation energy ( $\text{mJ}/\text{cm}^2$ )



rinsing

Developing  
unit

Mesh stretching

insolator

Atelier côté insolateur

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# Bulk done (04/2010 to 10/2010)

|                  | Goal                 | Dimension PCB | Active area (cm) | number |
|------------------|----------------------|---------------|------------------|--------|
| <b>Lab TESTS</b> |                      |               |                  |        |
|                  | PCB Test Equipements | 250/280       | 200/200          | 12     |
|                  | PCB RD1              | 120/140       | 95/95            | 18     |
|                  | PCB Test Mèche Fine  | 120/140       | 95/95            | 5      |
| <b>Projects</b>  |                      |               |                  |        |
|                  | SLHC                 | 200/280       | 100/100          | 4      |
|                  | MIMAC                | 180/180       | 110/110          | 7      |
|                  | CLAS 12 (TF10)       | 250/360       | 57/100           | 11     |
|                  | DETFROST             | D=110         | D= 90            | 3      |
|                  | FORFIRE              | D=70          | 41/41            | 3      |
|                  | COSMULTI (2 faces)   | 340/410       | 260/260          | 1      |
|                  | AT- TPC              | 290/320       | D= 270           | 4      |
|                  | Vrai/ Faux 2D        | 115/130       | 60/60            | 2      |
|                  |                      |               |                  |        |
|                  | Total                |               |                  | 70     |

Bulk done at Saclay by the MPGD workshop team  
(5 persons for 2 FTE )

# Double side bulk

Micromegas Double sided bulk for cosmic bench

- Fine spatial resolution: 200  $\mu\text{m}$  pitch
- Large active area: 260 x 260 mm
- Low amount of electronic channel: 72

The idea is to multiplex the strips and to remove the ambiguity by doubling the detectors (one thin multiplex strips and one large strips)

The DS bulk will be used on cosmic test bench to characterize CLAS12 detectors: 2 scintillators + 4 DS (2 XY).

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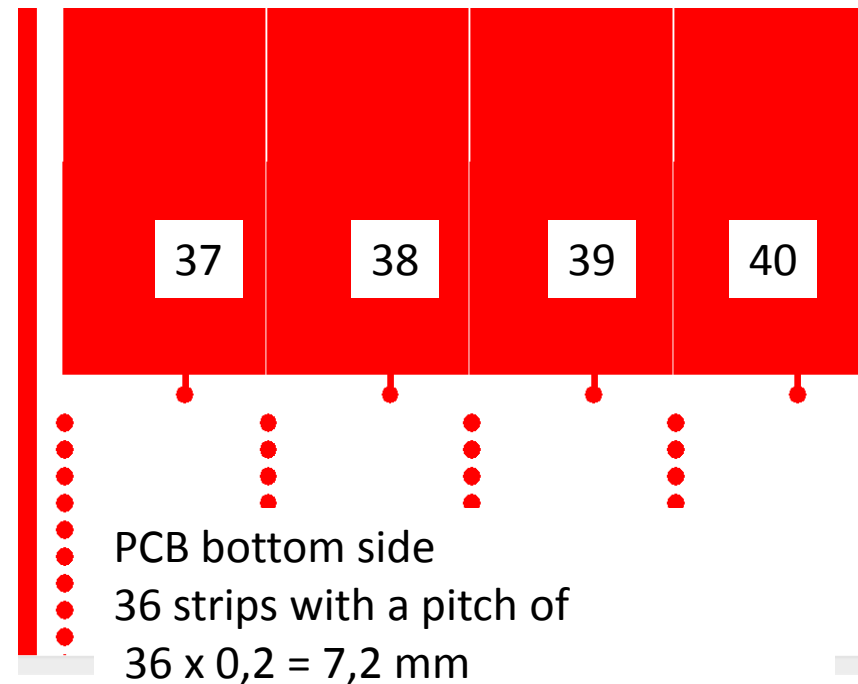
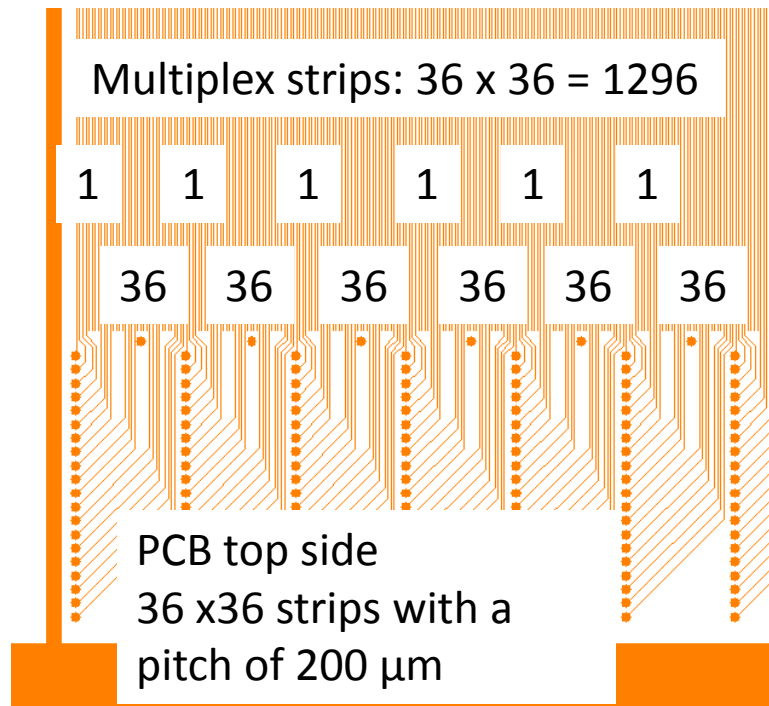


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# DS Bulk PCB layout

The PCB is a 4 layer with thin strips on top and large strips on bottom. Inner layers for fine strips multiplexing and shielding between active areas.

Thickness 0,8 mm. one 72 unique connector for AFTER readout





***Clas12 double sided bulk for cosmic bench***



# DS bulk realization & tests

- Realization:
  - The top side was first equipped with photoresist and woven mesh.
  - Bottom side equipped with photoresist and woven mesh.
  - UV exposure on both sides and simultaneous development.
  - Realization of DS #2 to #4 end of October et Saclay
- Test
  - test at air OK, test with 5% isobutane under way.
- Cosmic test bench operational in November

# Mesh segmentation

- Segmentation of the mesh on a the active area using a PCB milling machine with 200 to 400  $\mu\text{m}$  diameter tool.
- Possible goal:
  - Lower the capacitance for large bulk surface
  - Divide the “dead time blindness” when sparking
  - Several gain on same detector
  - Read the mesh for XY detection or ambiguity removing when multiplexing

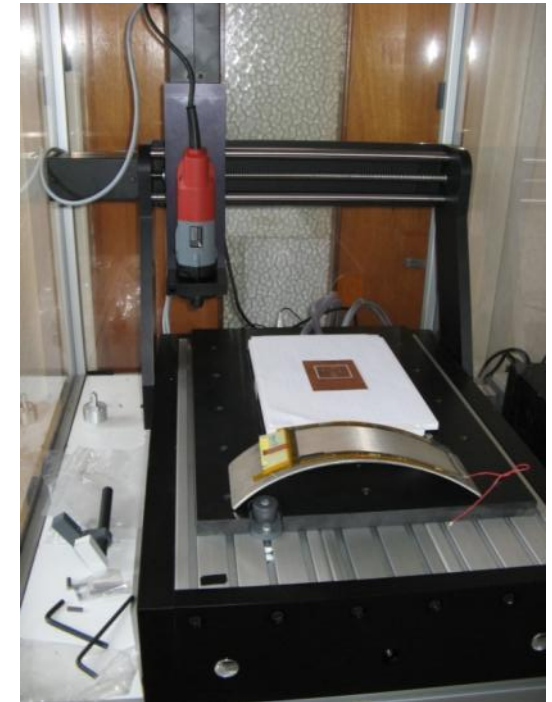
# PCB machining

Originally made to create PCB: 600 x 400 x 120 mm

- This machine can first record the planarity of the bulk and then mill following the flatness.
- The milling precision is less than  $10\ \mu\text{m}$
- Optical cameras for tool position



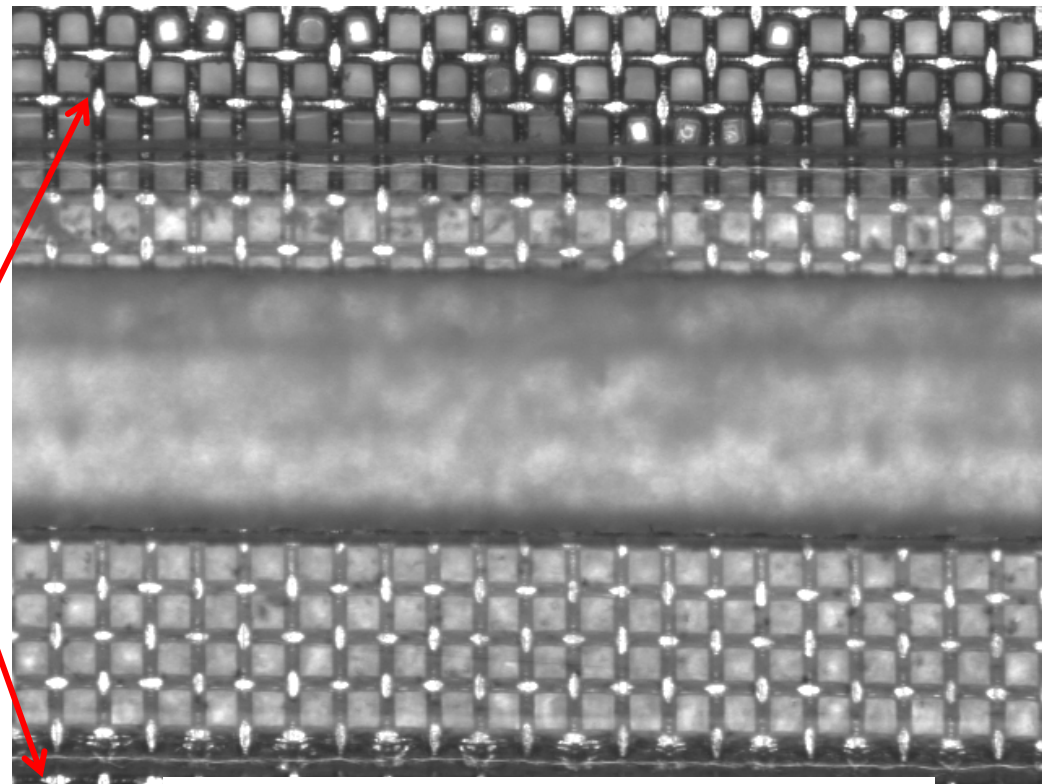
Machine and control PC



Machine clas12 prototype

# Mesh segmentation

- The bulk is created with wall of photoresist where the mesh will be cut.
- The thinner wall made to work are  $500\ \mu\text{m}$
- The strips are not damage (milling deepness of  $80\ \mu\text{m}$ ) on  $10\ \text{cm}$  active area



Active  
area

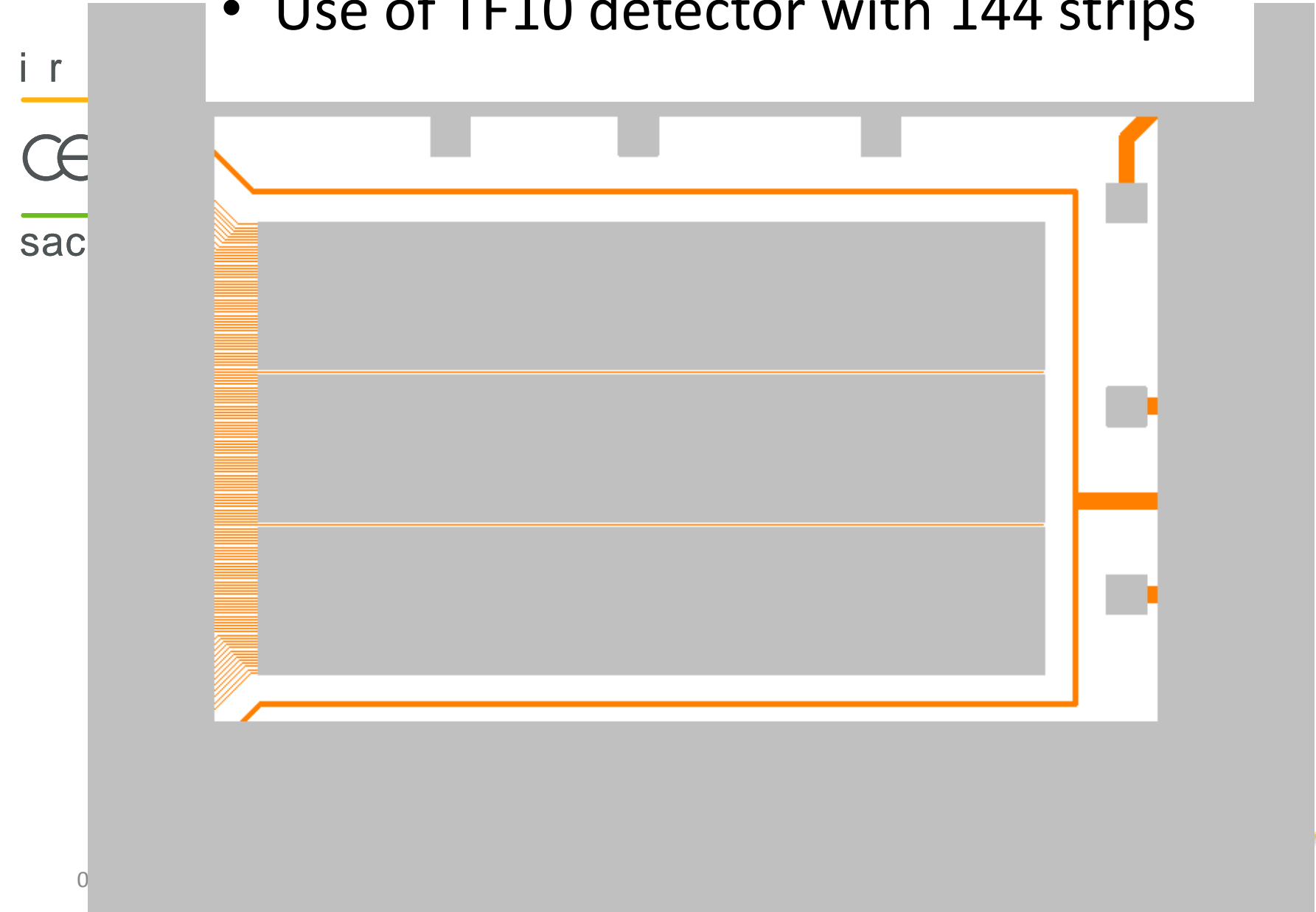
Wall  
thickness  
 $1\ \text{mm}$

$500\ \mu\text{m}$

$300\ \mu\text{m}$  cut on  $90\ \mu\text{m}$  deepness

# Mesh segmentation layout

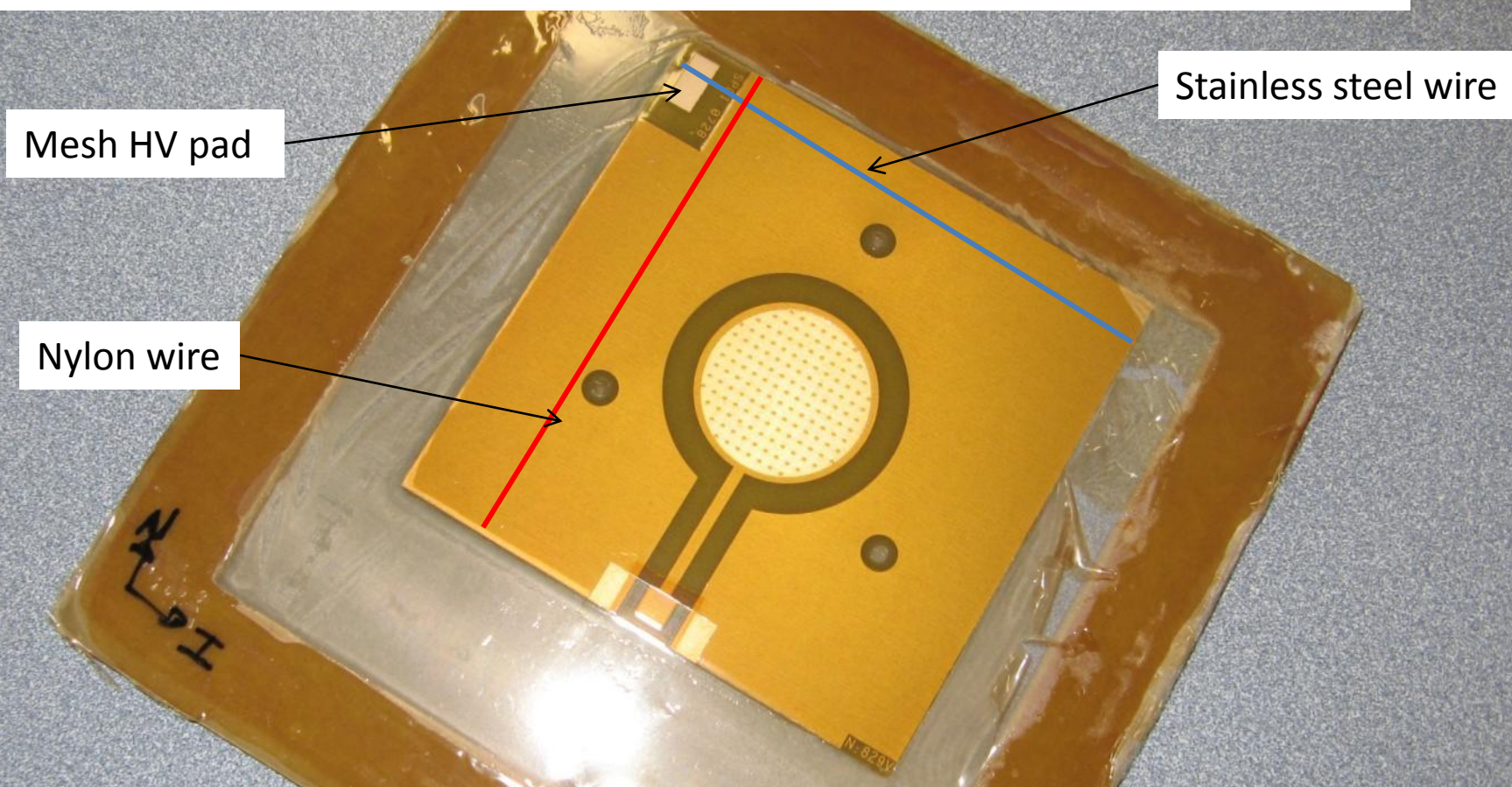
- Use of TF10 detector with 144 strips



# Mesh segmentation test

- The mesh was divided in 3 sectors A, B and C.
  - Mesh B and strip from B region were tested (ORTEC 142b and AFTER) with Fe55 while different tuning on mesh A and C were done
  - NO effect seen (counting rate, gain, DE/E,...) when mesh A and C are sparking (600 V with 5  $\mu$ A limitation)
- Future realization and test:
  - Segmentation on larger detector
  - With thinner photoresist wall
  - Mesh segmented, perpendicular to anode strip, in 1 mm “mesh strips” for mesh readout (AFTER adaptation for positive charge): XY detector !!!

# Bulk with exotic woven mesh (stainless steel and nylon) for GANIL test (J. PANCIN)



The mesh HV pad allowed voltage only on several wire out of the active area !!! ☹️ 😊 😊 😊

Tested after removing the photoresist on one side.

No positive test for nylon charging issue. To be continued.

# Bulk with thin mesh (A . GIGANON)

- Goal: make a bulk detector with thin electroformed mesh
  - Several detector were made with 5  $\mu\text{m}$  nickel mesh taken from old compass detector
  - After two tentative we succeeded in obtaining a bulk with no default. The mesh was not stretched yet at this stage.
  - Further test with Veco mesh (10  $\mu\text{m}$  Al) in coming month

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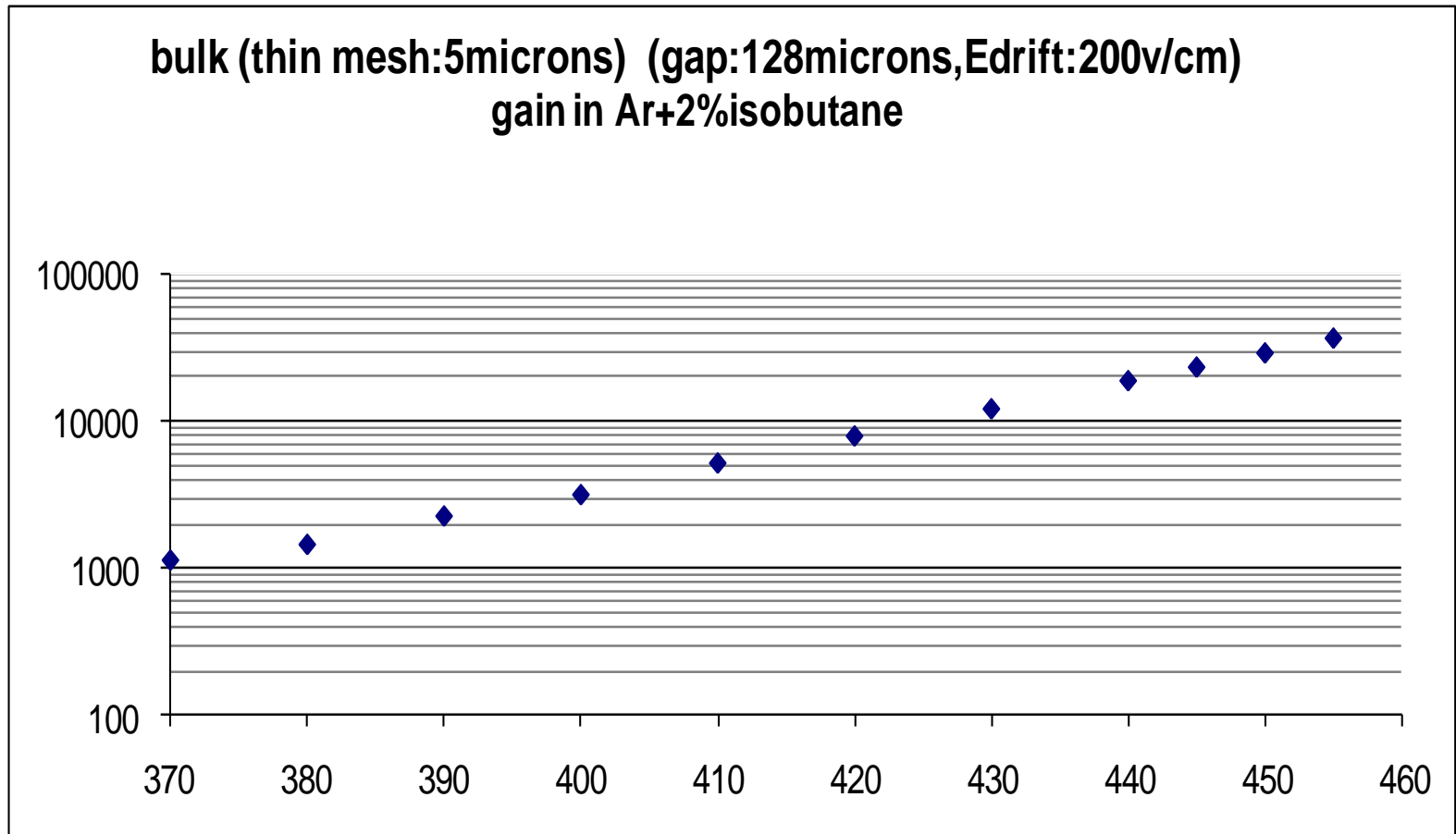
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# Gain curve

Bulk with thin mesh (thickness:5 microns)



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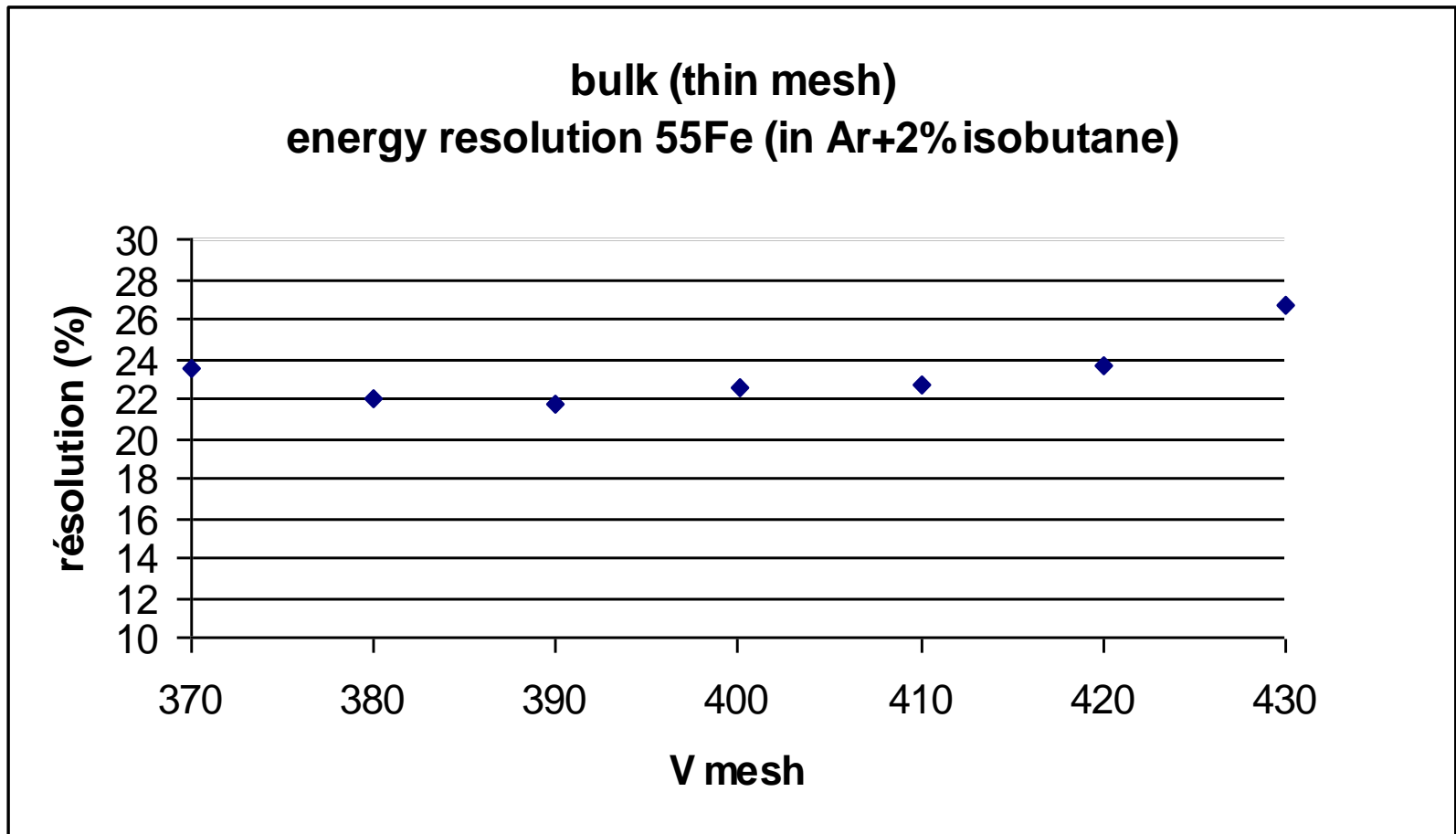
# Thin mesh

Energy resolution (55Fe) with non stretched mesh

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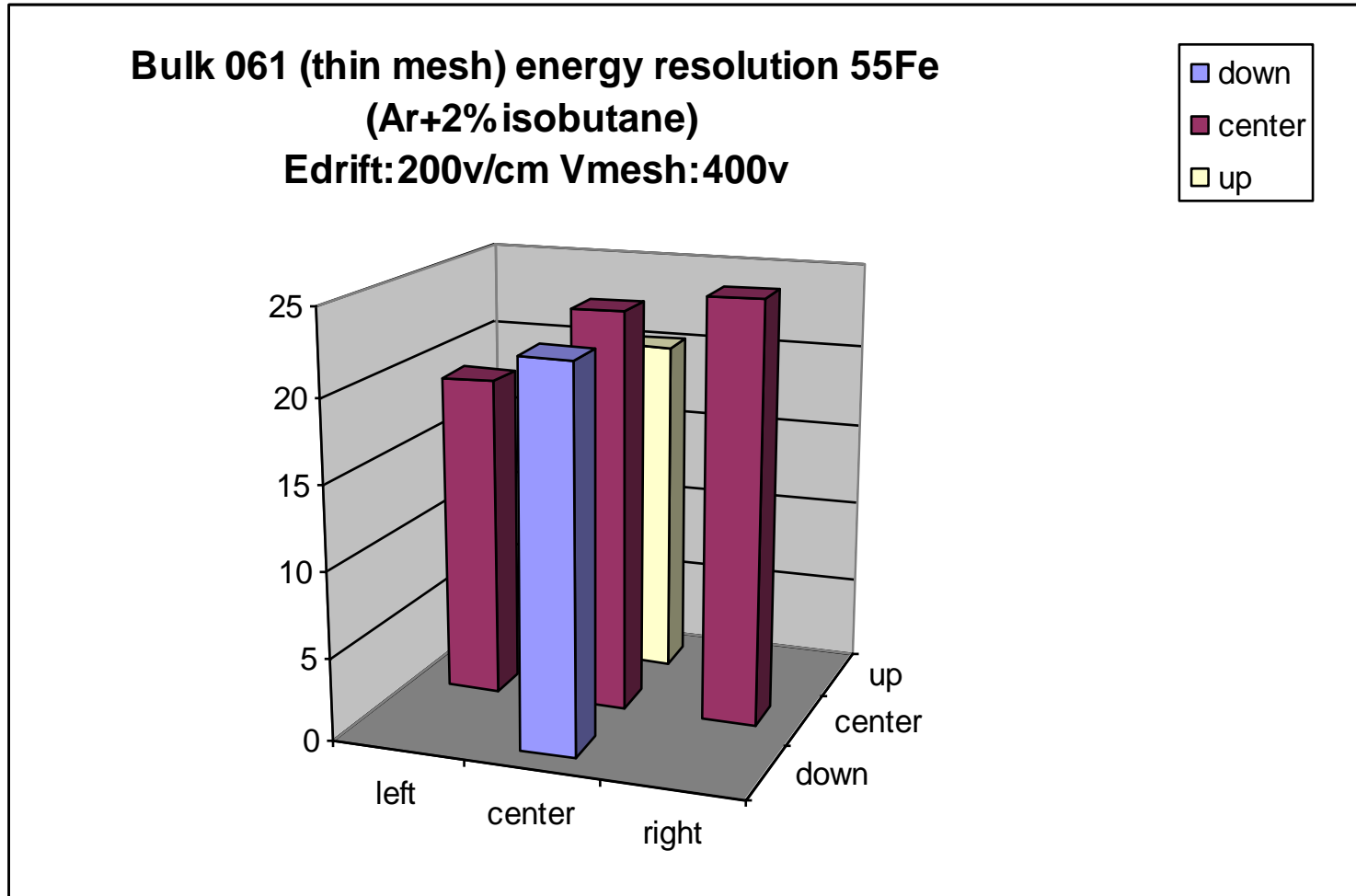
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# Thin mesh

## Energy resolution 55Fe (scanning)

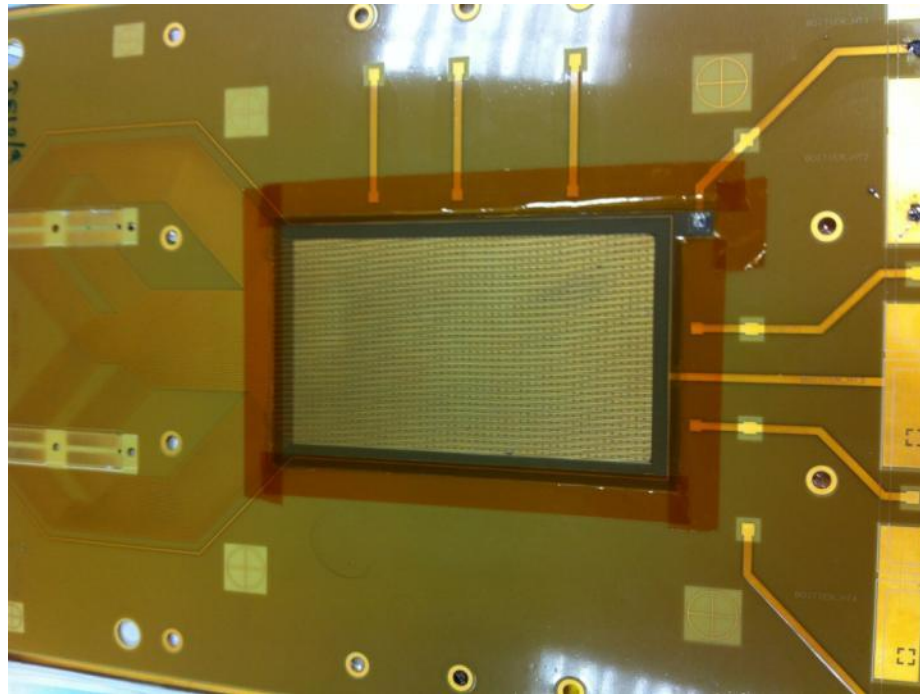


# Multi layer bulk (A. GIGANON)

- In order to make R&D on bulk with multistage mesh we have made tests to polymerize several layer of photoresist.
  - 8 layers of photoresist were laminated to obtain 500  $\mu\text{m}$  pillars.
  - Next step will be integration of 2 meshes on a bulk prototype (one mesh at 128  $\mu\text{m}$  and one at 600  $\mu\text{m}$ ).
    - Two possible techniques:
      - Insulation at once of all layers
      - Insulation before and after each mesh deposition

# Bulk with thick mesh

- A bulk was made using 265/50 Bopp mesh (thickness 50  $\mu\text{m}$  after lamination (special order thanks to RD51)). This mesh is 10 time less expensive than SDC 45/18
  - The amplification gap was 192  $\mu\text{m}$
  - Gain lower than “normal” bulk
  - Tests no yet concluding for spark region due to defect while making the bulk



# Pillar R&D

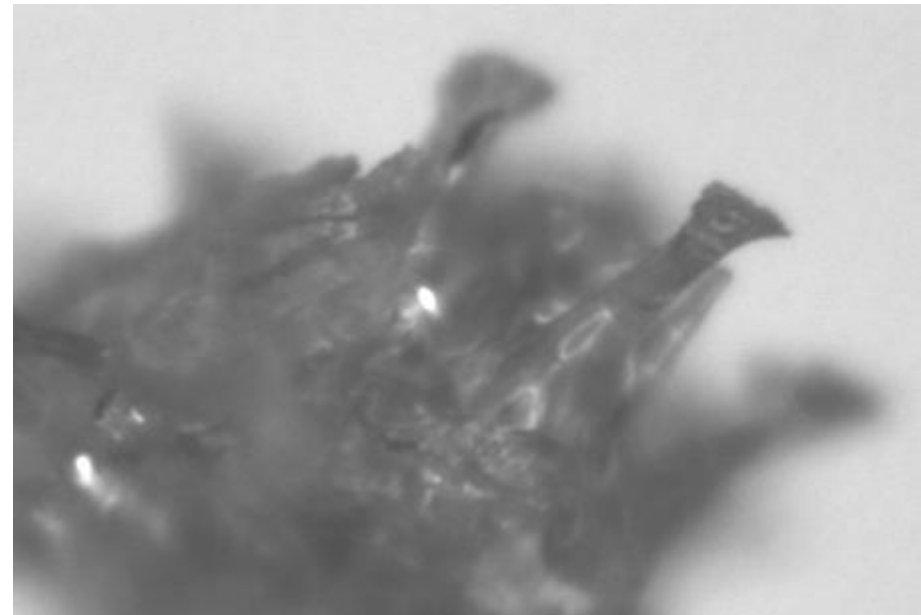
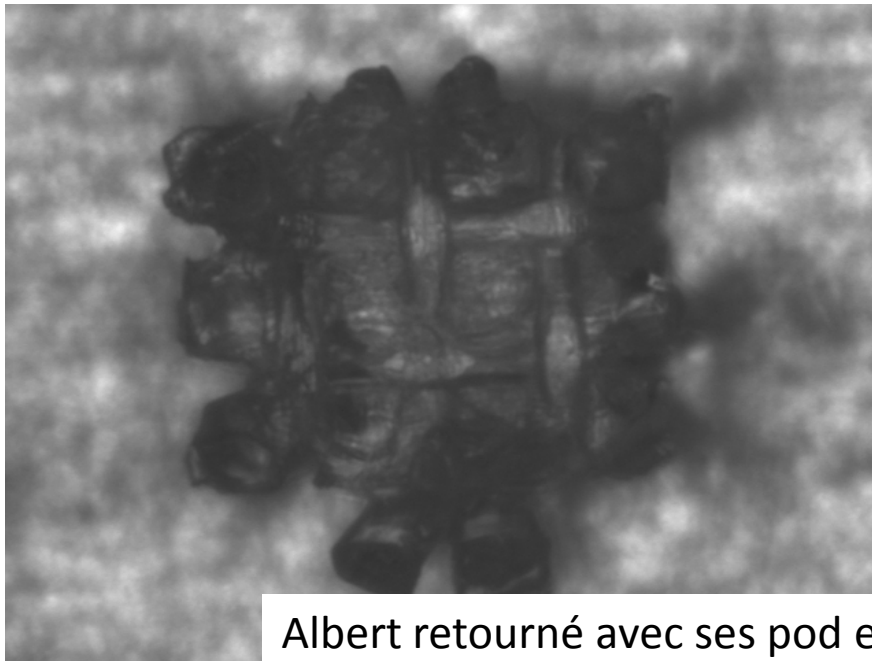
When polymerize through the mesh the pillar under the mesh are equipped with “pods”. This could explain the sparking issue when first HV cooking (up to 900 V in air)

Test with double insulation are under way.

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Albert retourné avec ses pod en l'air (partie de pod en l'air...)

Albert possède 8 à 9 pods

# Summary

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- The Saclay MPGD workshop allows us to have plenty R&D underway
- Ideas can become reality and tested in some 48 hours
- The workshop is open for R&D to the RD51 collaboration.
- Contact person:
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